

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Original) An exposure apparatus comprising:

an exposure region for irradiating exposure light to a substrate via an optical system

and a liquid, and

a measurement region for obtaining information relating to the position of the

substrate in advance of exposure, wherein

the exposure apparatus moves the substrate between the exposure region and the

measurement region to perform exposure of the substrate, wherein

the exposure apparatus further comprising:

a penetration shielding mechanism that prevents the penetration of the gas in the

vicinity of the exposure region to the measurement region.

2. (Original) An exposure apparatus according to Claim 1, wherein

the penetration shielding mechanism is an air conditioning system provided on the

exposure apparatus.

3. (Original) An exposure apparatus according to Claim 2, wherein the air conditioning

system further comprises:

a chamber, which includes the exposure region and the measurement region, and

a blower part that makes gas within the chamber flow from the measurement region

toward the exposure region.

4. (Original) An exposure apparatus according to Claim 3, wherein

the blower part further comprising:
an intake port formed on the measurement region side, and
an exhaust port formed on the exposure region side.

5. (Previously Presented) An exposure apparatus according to Claim 2, wherein
the air conditioning system comprises a shielding part that prevents the passage of gas
between the exposure region and the measurement region.
6. (Original) An exposure apparatus according to Claim 5, wherein
the shielding part is an air curtain.
7. (Previously Presented) An exposure apparatus according to Claim 2, wherein
an intake port and an exhaust port are respectively formed in the exposure region and
the measurement region.
8. (Original) An exposure apparatus according to Claim 1, wherein
the penetration shielding mechanism further comprising:
a suction mechanism that sucks the gas of the exposure region.
9. (Original) An exposure apparatus comprising:
an exposure region for irradiating exposure light to a substrate via an optical system
and a liquid, and
a measurement region for obtaining information relating to the position of the
substrate in advance of exposure, wherein

the exposure apparatus moves the substrate between the exposure region and the measurement region to perform exposure of the substrate, wherein
the exposure apparatus further comprising
an intake part that individually supplies a gas to the exposure region and the measurement region respectively.

10. (Original) An exposure apparatus according to Claim 9, wherein
the properties of the gas supplied to the exposure region and the gas supplied to the measurement region are mutually different.

11. (Original) An exposure apparatus comprising:
an exposure region for irradiating exposure light to a substrate via an optical system
and a liquid, and
a measurement region for obtaining information relating to the position of the substrate in advance of exposure, wherein
the exposure apparatus moves the substrate between the exposure region and the measurement region to perform exposure of the substrate, wherein
the exposure apparatus further comprising
an intake part, which supplies a gas to at least one of the exposure region and the measurement region, and
an exhaust part, which respectively independently exhausts the gas in the vicinity of the exposure region and the gas in the vicinity of the measurement region.

12. (Previously Presented) An exposure apparatus according to Claim 9, wherein
the exposure apparatus further comprising

a penetration shielding mechanism between the exposure region and the measurement region which prevents the gas in the vicinity of the exposure region from penetrating to the measurement region.

13. (Previously Presented) A device manufacturing method that includes a lithography process, wherein

an exposure apparatus of Claim 1 is used in the lithography process.

14. (New) An exposure apparatus according to Claim 11, wherein
the exposure apparatus further comprising
a penetration shielding mechanism between the exposure region and the measurement region which prevents the gas in the vicinity of the exposure region from penetrating to the measurement region.

15. (New) A device manufacturing method that includes a lithography process, wherein
an exposure apparatus of Claim 9 is used in the lithography process.

16. (New) A device manufacturing method that includes a lithography process, wherein
an exposure apparatus of Claim 12 is used in the lithography process.